



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR
REMOVING PHOTORESIST AND/OR
RESIST RESIDUE AT PRESSURES
RANGING FROM AMBIENT TO
SUPERCRITICAL

Confirmation No.: 8934

Group Art Unit: 1746

Examiner: B.S. Carrillo

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(37 CFR 1.8(a))**

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Dated: 09/27/2004

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Dated: September 27, 2004

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